## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

- 1. (Canceled)
- 2. (Previously Canceled)
- 3. (Canceled)
- 4. (Previously Canceled)
- 5. (Canceled)
- 6. (Previously Canceled)
- 7. (Canceled)
- 8. (Previously Canceled)
- 9. (Currently Amended) A substrate treating apparatus comprising:
- a support means that supports for supporting and spinning a substrate;
- a cleaning solution supply <u>means having a nozzle for supplying</u> that supplies a cleaning solution having ozone dissolved therein to said substrate;

an ultraviolet emitter means for emitting than emits ultraviolet light to said substrate; and wherein a control which controls the ultraviolet emitter so that, during a cleaning process in which said cleaning solution is supplied from said cleaning solution supply means to said substrate supported and spun by said support means, said ultraviolet emitter emitting means emits ultraviolet light to said cleaning solution supplied to said substrate and forming a puddle on an upper surface of said substrate.

- 10. (Previously Amended) An apparatus as defined in claim 9, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.
- 11. (Currently Amended) An apparatus as defined in claim 9, wherein said cleaning solution includes a base including base adding means for adding a base to the cleaning solution.

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12. (Currently Amended) An apparatus as defined in claim 10, wherein said cleaning solution has a base added thereto including base adding means for adding a base to the cleaning solution.

## 13. - 16. (Previously Canceled)

17. (Previously Amended) A substrate treating method for removing film from a substrate by supplying a treating solution thereto, comprising the steps of:

supplying said treating solution having ozone dissolved therein to said substrate; and subsequently irradiating said treating solution supplied to said substrate with ultraviolet light.

- 18. (Previously Canceled)
- 19. (Canceled)
- 20. (Previously Canceled)
- 21. (Canceled)
- 22. (Previously Canceled)
- 23. (Canceled)
- 24. (Previously Canceled)
- **25.** (Currently Amended) A substrate treating apparatus for removing film from a substrate by supplying a treating solution thereto, comprising:
  - a support means for supporting and spinning that supports said substrate;
- a treating solution supply <u>means having a nozzle for supplying</u> that supplies said treating solution having ozone dissolved therein to said substrate;

an ultraviolet <u>emitting means for emitting</u> <del>emitter that emits</del> ultraviolet light to said substrate; and

wherein a control that controls the ultraviolet emitter so that, during a film removing process in which said treating solution is supplied from said treating solution supply means to said substrate supported and spun by said support means, said ultraviolet emitter emitting means

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emits ultraviolet light to said treating solution supplied to said substrate and forming a puddle on an upper surface of said substrate.

- **26.** (Previously Amended) An apparatus as defined in claim 25, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.
- 27. (Currently Amended) An apparatus as defined in claim 25, wherein said treating solution has a base added thereto including base adding means for adding a base to the treating solution.
- 28. (Currently Amended) An apparatus as defined in claim 26, wherein said treating solution has a base added thereto including base adding means for adding a base to the treating solution.

29. - 32. (Previously Canceled)

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